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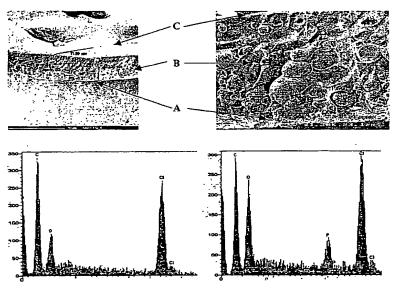
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[Continued on next page]

(54) Title: POLYMER COMPOSITION



(57) Abstract: Polymer composition comprising: 1) a polymer (P1) comprising at least 50 % by weight of monomeric units derived from an ethylenically unsaturated monomer (M1), and 2) at least one co-oligomer (O1) comprising at least: a) a component (A) comprising at least one monomeric unit identical to that derived from the monomer (M1) on which the polymer (P1) is based, and b) a component (B) comprising at least one monomeric unit (m2), derived from an ethylenically unsaturated monomer, carrying at least one group chosen from the following groups: -C<sub>2</sub>H<sub>2s+1</sub> with a between 6 and 30; -(CH<sub>2</sub>)<sub>b</sub>-C<sub>c</sub>F<sub>2c+1</sub> with b between 1 and 11 and c greater than or equal to 5; -(CH<sub>2</sub>)<sub>d</sub>-(Si(CH<sub>3</sub>)<sub>2</sub>-O)<sub>e</sub>-Si(CH<sub>3</sub>)<sub>3</sub> with d between 1 and 11 and e between 1 and 1000; -COOH; -S0<sub>3</sub>H, and the phosphonate groups - $PO(OH)(OR_1)$  with  $R_1$  being a hydrogen atom or an alkyl radical containing from 1 to 11 carbon atoms.





PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.

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